# Fourth Semester B.E. Degree Examination, June/July 2019 Synthesis and Processing Techniques

Time: 3 hrs. Max. Marks: 80

Note: Answer any FIVE full questions, choosing ONE full question from each module.

### Module-1

- a. Mention different types of CVD techniques. Explain in detail about CVD method including both hot wall and cold wall set up. (10 Marks)
  - b. With a neat schematic diagram explain the Langmuir Blodgett technique in detail for thin film making. (06 Marks)

### OR

- 2 a. Mention some of the application of arc discharge method and explain briefly about working of arc discharge method. (10 Marks)
  - b. Explain the working process of loser pyrolysis with neat schematic diagram. (06 Marks)

# Module-2

- 3 a. Define Sol and Gel. Explain in detail about Sol-Gel process along with proper diagram of Sol-Gel options. (10 Marks)
  - b. Explain the process of solution combustion method along with proper flow chart in detail. (06 Marks)

### OR

- 4 a. Explain in detail about co-precipitation and arrested precipitation methods for synthesizing nanoparticles. (08 Marks)
  - b. Explain the working process of photochemical synthesis method with an example of nanoparticles synthesizing in detail. (08 Marks)

### Module-3

- 5 a. Explain in detail about growth mechanism and kinetics and rate determining steps in VLS method. (10 Marks)
  - b. Write short notes on Flame Spray Pyrolysis.

6 a. Explain briefly about VLS growth of nanowires and control of the size of the nanowires.
(10 Marks)

OR

b. Explain in detail about gas condensation working process in detail.

## (06 Marks)

(06 Marks)

### Module-4

- 7 a. Draw Electron Beam Lithography set up and explain working process in detail. (10 Marks)
  - b. Define nanolithography and explain in brief about nanolithography based on AFM.

### (06 Marks)

### OR

- **8** a. Write a note on oxidation and metallization and mask and its application.
- (10 Marks)
- b. Explain briefly about Ion beam Lithography with schematic diagram.

Module-5

- 9 a. Explain the process of developing photo catalyst inserted into surface of porous alumina silica. (10 Marks)
  - b. Explain instantaneous nano foaming method for fabrication of closed porosity silica particle.
    (06 Marks)

OR

- 10 a. Explain the fabrication technique of organic nano crystals and their optical properties and materialization. (10 Marks)
  - b. Explain briefly about surface modification of in-organic nanoparticles by organic functional groups (06 Marks)

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